

<b>Notice of References Cited</b>	Application/Control No. 10/509,370	Applicant(s)/Patent Under Reexamination SUGAWARA ET AL.	
	Examiner Eric B. Chen	Art Unit 1765	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2002/0009892	01-2002	COHEN et al.	438/710
*	B	US-6,451,641	09-2002	Halliyal et al.	438/200
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf, Silicon Processing for the VLSI Era, 2002, Lattice Press, Vol. 4, pp. 145-46.
	V	Rossnagel et al., Handbook of Plasma Processing, 1990, Noyes Publications, p. 198.
	W	Kern, Handbook of Semiconductor Wafer Cleaning Technology, 1993, Noyes Publications, pp. 224-26.
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.